

LISTING OF THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. - 8. (Canceled)

9. (Currently Amended) A substrate treating apparatus for removing organisms from substrates, comprising:

a support means including a chuck rotatable by a motor for supporting and spinning a substrate in a horizontal plane;

a cleaning solution supply means including a nozzle for supplying a cleaning solution having ozone dissolved in deionized water to an upper surface of said substrate;

an ultraviolet emitter means including UV lamps and a reflector for emitting ultraviolet light to said substrate; said ultraviolet emitting means emitting ultraviolet light under atmospheric conditions to said substrate from an irradiating position above said support means; and

a controller for rotating said support means supporting said substrate, the controller controls supplying said cleaning solution from said nozzle of said cleaning solution supply means to a spin center of said substrate to form a puddle on an upper surface of each substrate supported and spun, and, during this cleaning process, and the controller controlling supplying power to said UV lamps to emit ultraviolet light to said cleaning solution supplied to said substrate and forming a puddle ~~on an upper surface of said substrate.~~

10. (Previously Presented) An apparatus as defined in claim 9, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.

11. (Previously Presented) An apparatus as defined in claim 9, including base adding means for adding a base to the cleaning solution.

12. (Previously Presented) An apparatus as defined in claim 10, including base adding means for adding a base to the cleaning solution.

13. - 24. (Canceled)

25. (Currently Amended) A substrate treating apparatus for removing photoresist film from a substrate by supplying a treating solution thereto, comprising:

a support means including a chuck rotatable by a motor for supporting and spinning said substrate in a horizontal plane;

a treating solution supply means including a nozzle for supplying said treating solution having ozone dissolved in deionized water to an upper surface of said substrate;

an ultraviolet emitting means including UV lamps and a reflector for emitting ultraviolet light to said substrate, said ultraviolet emitting means emitting ultraviolet light under atmospheric conditions to said substrate from an irradiating position above said support means; and

a controller for rotating said support means supporting said substrate, the controller controls supplying said cleaning solution from said nozzle of said cleaning solution supply means to a spin center of said substrate to form a puddle on an upper surface of each substrate supported and spun, and, during this cleaning process, and the controller controlling supplying power to said UV lamps to emit ultraviolet light to said cleaning solution supplied to said substrate and forming a puddle ~~on an upper surface of said substrate.~~

26. (Previously Presented) An apparatus as defined in claim 25, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.

27. (Previously Presented) An apparatus as defined in claim 25, including base adding means for adding a base to the treating solution.

28. (Previously Presented) An apparatus as defined in claim 26, including base adding means for adding a base to the treating solution.

29. - 32. (Canceled)

33. (Currently Amended) A substrate treating apparatus for cleaning substrates by removing organisms therefrom, comprising:

a support rotatable by a motor for supporting and spinning a substrate;

a cleaning solution supply having a nozzle for supplying a cleaning solution having ozone dissolved therein to an upper surface of said substrate;

an ultraviolet emitter that emits ultraviolet light onto said substrate from an irradiating position above said support; and

a controller that controls rotation of the support, the controller controlling ~~controls~~ the supplying of said cleaning solution from said nozzle of said cleaning solution supply wherein the nozzle is capable of forming in a manner that forms a puddle on ~~[[an]]~~ the upper surface of said substrate, and the controller controlling ~~, during this cleaning process, controls~~ supplying power to said emitter to emit ultraviolet light to said cleaning solution supplied to said substrate.

34. (Previously Presented) An apparatus as defined in claim 33, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.

35. (Previously Presented) An apparatus as defined in claim 33, including an auxiliary supply for adding a base to the cleaning solution.

36. (Previously Presented) An apparatus as defined in claim 34, including an auxiliary supply for adding a base to the cleaning solution.

37. (Previously Presented) An apparatus as defined in claim 33, wherein:
the support includes a chuck rotatable by a motor for supporting and spinning said substrate in a horizontal plane; and
the ultraviolet emitter includes UV lamps and a reflector for emitting ultraviolet light to said substrate.